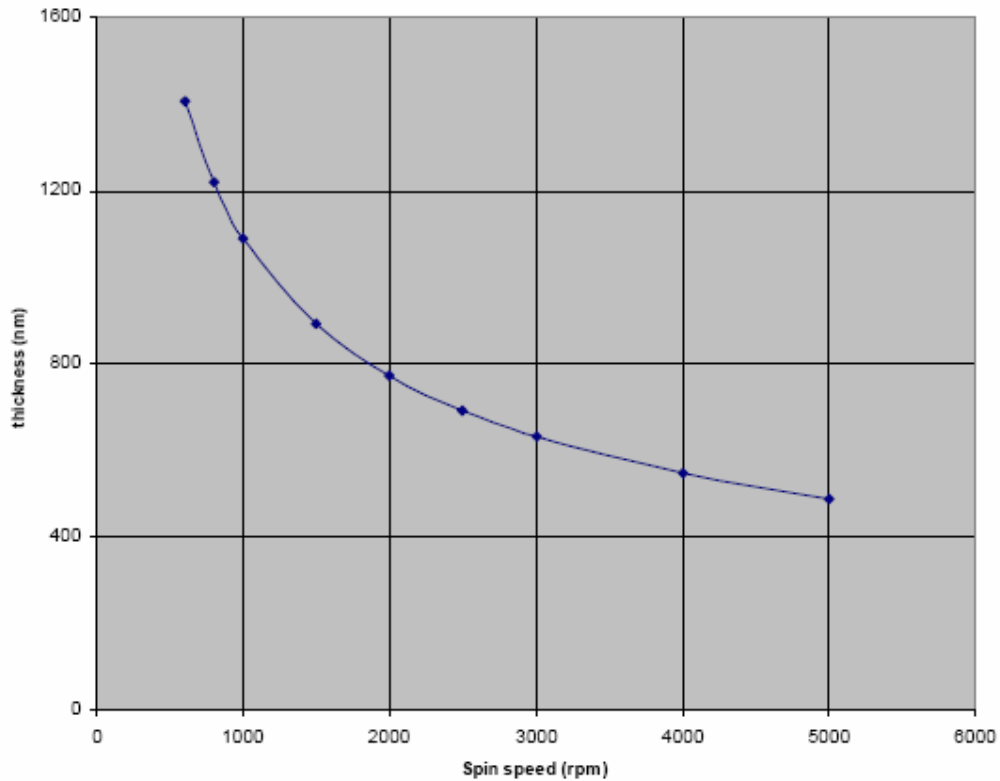


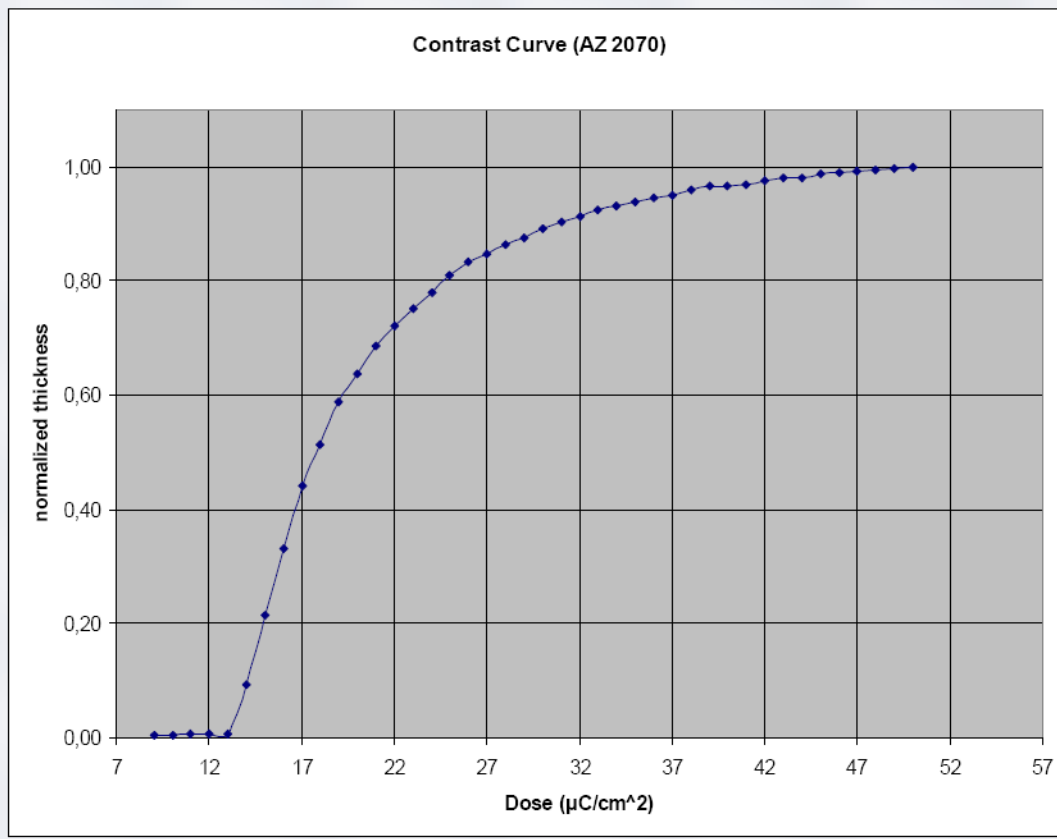
Datasheet Preview: „AZ 2070 500nm-grade“
Process suggestion

- **Substrate:** Si-Wafer
- **Resist thickness:** 545nm / 4000rpm (without exposure)
- **Resist Track:** Hamatech Modutrack 2000
- **Exposure:** Vistec SB352HR with Prox Correction
- **Test Design:** 150, 200, 400 and 750nm Lines
- **Developer:** AZ 826, Double Puddle 2 x 35s
- **Delays (PCD, PED):** 0h
- **PAB:** 100°C/60s
- **PEB:** 110°C/60s

Spincurve:



Contrast Curve:



Dense Lines (nm)	150	200	400	750
Dose Factor	1,435	1,401	1,401	1,401

